

SHEET 1 OF 1

INFORMATION DISCLOSURE CITATION IN AN APPLICATION.				ATTY. DOCKET NO. 49959-220		SERIAL NO. 09/986,137	
(PTO-1449)				APPLICANT Gilad ALMOGY, et al.			
				FILING DATE November 07, 2001		GROUP 2881	
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear		
		US 5,090,803	02/25/92	Ames et al.			
		US 5,238,178	08/24/93	Demdinger et al.			
		US 4,500,202	02/19/85	Smyth			
		US 3,963,354	08/15/76	Feldman et al.			
		US 5,198,900	03/23/93	Pettersen			
		US 6,108,090	08/22/00	Ishihara			
		US 5,783,833	07/21/98	Sugaya et al.			
		US 6,208,411	03/27/01	Vaez-Iravan			
FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Codes, Number & Kind Codes (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation	
		EP 1058111 A2	12/08/00	Europe		Yes	No
		WO 97/34171	09/18/97	PCT			
		WO 99/48041	09/23/99	PCT			
		EP 1138254 A1	10/04/01	Europe			
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.					
		"Quality control and process observation for the micro assembly process", Tilo Pfeiler et al, MEASUREMENT, INSTITUTE OF MEASUREMENT AND CONTROL, vol. 30, no. 1, July 2001, pp. 1-18.					
EXAMINER 				DATE CONSIDERED 11-17-04			

*EXAMINER: Initial reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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				APPLICANT Gilad ALMOGY, et al.			
				FILING DATE November 07, 2001		GROUP 3662	
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code ₂ (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear		
		US 6,040,909	03/21/00	Hasegawa et al.			
		US 6,248,988	06/19/01	Krantz			
		US 6,130,428	10/10/00	Pasch			
		US 5,932,968	08/03/99	Schneider et al.			
		US 3,894,332	07/15/75	Nathanson et al.			
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		US					
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EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Codes - Number 4 - Kind Codes (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation	
						Yes	No
		GB 2339960 A	02/09/00	United Kingdom			
		WO 01/84585 A1	11/08/01	PCT			
		WO 02/23172 A2	03/21/02	PCT			
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		WO 01/09920 A1	02/08/01	PCT			
		WO 02/15223 A1	02/21/02	PCT			
		WO 02/23580 A1	03/21/02	PCT			
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item, book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.					
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		"Microlens arrays with spatial variation of the optical functions", Hessler, Th., et al., Pure Appl. Opt. 6(1997) 673-681.					
		"A Microlens Direct-Write Concept for Lithography", Davidson, M., SPIE 3048, p. 346-355.					
		"Immersion lithography at 157 nm", Swilkes, M. et al., J. Vac. Sci. Technol. B, Vol. 19, No. 6, Nov/Dec 2001, pp. 2353-2356					
		"Liquid immersion deep-ultraviolet interferometric lithography", Hoffnagle, J. et al., Vac. Sci. Technol. B 17(6), Nov/Dec 1999, pp. 3306-3309					
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		"UV Thermoresists: Sub 100nm Imaging Without Proximity Effects", Gelbart, D. et al., SPIE Vol. 3676, pp. 786-793					
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Gilad ALMOGY, et al.

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US: PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS							
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						Yes	No
		WO 98/57151	12/17/98	PCT			
		0679864 A1	11/02/85	Europe			
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		2000088374	03/03/00	Japan		X Abstract	

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		Partial International Search Report dated 5/5/03.

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U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUB CLASS	FILING DATE	
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	5,900,637	5/4/1999	Smith				
	6,248,988	9/19/2001	Krantz				
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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUB CLASS	Translation	
						Yes	No
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	"Projection X-Ray Lithography Using Arrays of Zone Plates", M. Feldman, Electrical & Computer Engineering Department, pp. 136-144.						
	"Zone-plate-array lithography in the deep ultraviolet", Ihsan J. Djomehri et al., American Vacuum Society, 1998, pp. 3426-3429.						
	"Zone-Plate Array Lithography (ZPAL): A new maskless approach", D.J.D. Carter et al., Part of the SPIE Conference on Emerging Lithographic Technologies III, March 1999, pp. 324-332.						
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	"Lithographic patterning and confocal imaging with zone plates", Dario Gil et al., American Vacuum Society, 2000, pp. 2881-2885.						
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